

# The anisotropic dielectric function for copper phthalocyanine thin films

O.D. Gordan  , M. Friedrich and D.R.T. Zahn

Institut für Physik, Technische Universität Chemnitz, Reichenhainerstr. 70, D-09107 Chemnitz, Germany

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## Abstract

Copper phthalocyanine (CuPc) thin films were prepared by organic molecular beam deposition (OMBD) in high vacuum and ultra-high vacuum on passivated Si(1 1 1) using  $\beta$ -phase CuPc as source material. The substrates were kept at room temperature during the deposition. The IR peak positions indicate that the films consist mainly of  $\alpha$ -phase CuPc, while the relative intensities suggest that the films are anisotropic. The anisotropic dielectric function for these CuPc layers was determined from ellipsometric spectra using uniaxial models in the range from 0.73 to 5 eV.

**Keywords:** Ellipsometry; Infrared spectroscopy; Optical anisotropy; Organic molecular thin films; Copper phthalocyanine